



High temperature vapor phase reactions of nitrogen trifluoride with benzylic substrates

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ARTICLE INFO

Article history:

Received 11 February 2011
Received in revised form 2 March 2011
Accepted 3 March 2011
Available online 15 March 2011

Keywords:

Nitrogen trifluoride
Benzylic substitution
Radical abstraction
Difluoroalkylamines
 β -Elimination
Beckman rearrangement

ABSTRACT

At temperatures around 400 °C, nitrogen trifluoride (NF₃) readily reacts with benzylic substrates. Products vary with the substrate, but are all the result of difluoroamination at the benzylic position. Toluene and ethylbenzene produce benzonitrile. Cumene produces α -methylstyrene. Diphenylmethane produces benzanilide. Little or no direct fluorination or radical dimerization is observed.

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1. Introduction

1.1. Environmental issues of nitrogen trifluoride

Nitrogen trifluoride (NF₃) is the premier etching gas for the manufacture of silicon wafer computer chips as well as for plasma or thermal cleaning of Chemical Vapor Deposition chambers. World-wide production for 2008 was estimated at 4000 metric tons. While supposedly 96–98% of NF₃ is destroyed in the process of being used, atmospheric measurements indicate that more than the remaining 2–4% is getting into the atmosphere. According to research from UC, Irvine [1] and the Scripps Institute of Oceanography [2], nitrogen trifluoride is much more prevalent in the atmosphere than was estimated by industry. This is of great concern as NF₃ has a GWP of 17,000 and amounts to 10.5 million metric tons of CO₂ equivalent per year. For this reason, there have been calls to add NF₃ to the list of Kyoto Protocol reportable compounds. The studies indicated that the overall emissions are apparently being supplemented by leakages during production. However, such “leakages” would have to account for up to 16% of production, an unlikely scenario.

The venting of “off-specification” NF₃ by overseas manufacturing plants is a more plausible explanation for high atmospheric NF₃ levels. The specification for electronics grade NF₃ is “four nines”,

that is 99.99% or better. Any upsets in manufacturing conditions that produce “off-spec” NF₃ produce material that cannot be reworked or purified. With a critical temperature of –39.2 °C and a critical pressure of 45.28 bar, manufacturing sites cannot store any appreciable quantity of “off-spec” NF₃ and so are forced to vent it. Scrubbing technologies are not up to the task and 25–100% of the NF₃ escapes trapping [3]. It is unlikely that manufacturers will adopt more expensive technologies that to destroy the offending NF₃ waste stream. Unless an economical alternative is offered, venting will continue as required and the atmospheric concentration of NF₃ will continue to rise. Even governmental regulation is unlikely to stop the introduction of NF₃ into the atmosphere (refer to the Kyoto HFC-23 Offset Program where manufacturers intentionally produced waste to receive credit for its disposal) [4].

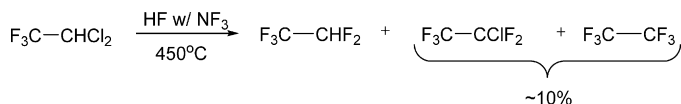
It is the overall goal of this project to develop chemistries that will allow manufacturers to convert off-specification NF₃ to commercially valuable compounds, thus giving them economic incentive to do so. The availability of such a process could reduce intentional emissions and mitigate the Global Warming impact of NF₃ production.

1.2. Precedent for reactivity

The utility of nitrogen trifluoride is due to its known decomposition at elevated temperatures. When heated to temperatures above 250 °C, NF₃ exudes fluoride radicals which are reactive with metals and metal oxides and are thus useful in etching the silicon surfaces of computer chips. The early literature

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Scheme 1. Literature evidence of fluorination by NF_3 .

gives examples of NF_3 reacting as a fluoride source with sulfur [5], non-metal and metal oxides [6,7] non-metal oxyhalides [8], cyanides [9], and phosphorus–sulfur compounds [10]. The nearest example to reaction with an organic compound is the reaction of NF_3 with COCl_2 . NF_3 has been shown to be able to add across select olefins to produce perfluoroamines [11].

Our own research has used NF_3 to prevent or remove the carbonaceous deposits that foul high temperature vapor phase catalysts [12]. In particular, chromium fluoride catalysts used for fluorine-for-chlorine exchange reactions in the manufacture of hydrofluorocarbons were kept active with a co-feed of NF_3 . Example reactions were the preparation of difluoromethane (HFC-32), pentafluoroethane (HFC-125) and tetrafluoroethane (HFC-134a) from the appropriate hydrochlorocarbons. During the course of these reactions, it was observed that some of the product was halogenated to a greater extent than the original starting material. For example, appreciable quantities (10%) of pentahaloethanes were observed during the hydrofluorination of chlorotrifluoroethane (HFC-133a) to tetrafluoroethane (HFC-134a) (Scheme 1).

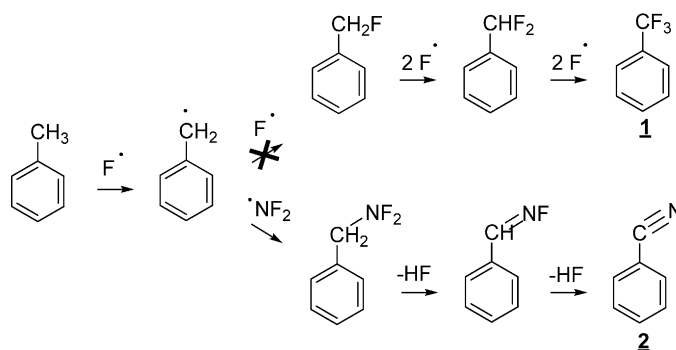
Similar by-product formation also results from the use of the oxidants Cl_2 or O_2 as a co-reagent. NF_3 appears to also be acting as an oxidizing agent. Whether the NF_3 is oxidizing the Cr^{III} catalyst to a reactive oxidation state, is oxidizing by-product HCl to Cl_2 , or is performing fluorine-for-hydrogen exchange directly is yet to be determined. It was none-the-less the intent of this project to harness the net fluorinating capability of NF_3 to perform fluorination reactions and produce commercially saleable hydrofluorocarbons.

2. Results and discussion

2.1. Reaction of NF_3 with toluene

It was assumed that at high reactor temperatures NF_3 would be generating F radicals and N_2 , such as it does in etching processes. The reaction we chose to utilize this chemistry was benzylic fluorination. Benzylic fluorination of toluene would be expected to generate benzyl fluoride, benzyl difluoride and benzotrifluoride in various proportions. Benzotrifluoride, **1**, is a valued compound that is considered to be an environmentally more acceptable substitute for dichloromethane (methylene chloride) in solvent applications.

In actuality, the results of the reaction of NF_3 with toluene were quite different. In a reaction performed at 400°C , the principle product was benzonitrile, **2**. A short retroanalysis reveals that rather than benzylic fluorination, benzylic difluoroamination is occurring. An initial F radical abstracts a benzylic proton and the resulting benzylic radical is quenched by difluoroamino radical. The resulting difluoroamine is unstable and eliminates HF twice to



Scheme 2. Reaction of NF_3 with toluene.

yield the isolated benzonitrile product (Scheme 2). This all occurs within the reactor (and not during aqueous work-up) as benzonitrile is also isolated when the product stream is alternatively vacuum stripped of HF . No fluorotoluenes or other light compounds were observed on GC. A complex mixture of heavy components made up the remaining mass balance.

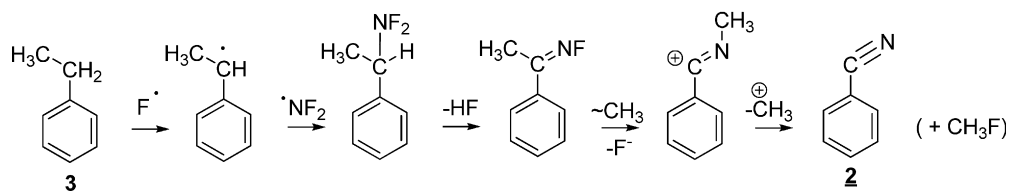
2.2. Reaction of NF_3 with ethylbenzene

With NF_3 clearly reacting via radical substitution at the benzylic position of toluene, we undertook the simple extension of the reaction to include 2° and 3° benzylic compounds. We were immediately surprised to see the results of reacting NF_3 with the 2° substrate, ethylbenzene, **3**. One might expect ethylbenzene to follow a similar mechanistic pathway as that of toluene. Indeed, difluoroamination at the benzylic position is apparently occurring, along with the elimination of one HF molecule. However at this point, the unstable fluoroimine intermediate apparently undergoes a Beckmann Rearrangement with subsequent fragmentation as the sole product of reaction is again benzonitrile, **2** (Scheme 3).

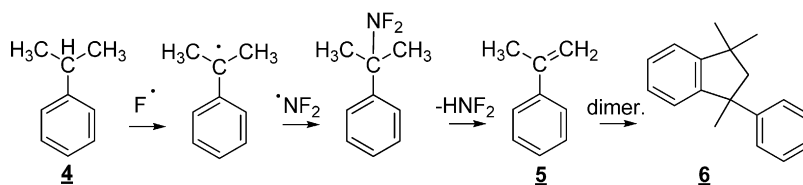
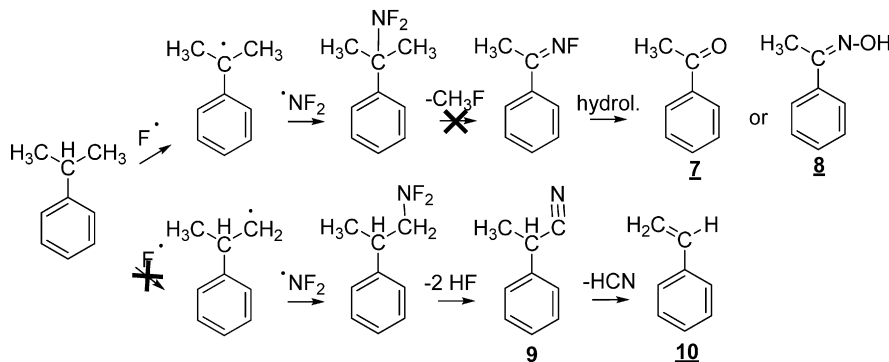
2.3. Reaction of NF_3 with cumene

The simplest toluene analog with a 3° benzylic position is cumene, **4**. Reaction of NF_3 with cumene yielded a single heavy product which was difficult to characterize by NMR. This heavy product could be induced to crystallize and was identified by X-ray crystallography as 2,3-dihydro-1,1,3-trimethyl-3-phenyl-1H-indene, **6** [13]. This complicated molecule is, in fact, one of the three known dimers of α -methylstyrene, **5**. So, it appears that cumene is reacting with NF_3 in the normal manner to form a benzylic difluoroamine, followed by an elimination of HNF_2 (Scheme 4).

One might expect cumene to follow the same course of reaction as ethylbenzene, that is, 3° substitution followed by CH_3F elimination (via Beckmann rearrangement). However, we saw no evidence of the products of CH_3F elimination such as acetophenone, **7**, or acetophenone oxime, **8** (Scheme 5). One might then suspect that selectivity had been lost and that difluoroamination is occurring at the 1° position with elimination



Scheme 3. Reaction of NF_3 with ethylbenzene.

Scheme 4. Reaction of NF_3 with cumene.Scheme 5. Unobserved reactions of NF_3 and cumene.

of HNF_2 occurring in the other direction. However, in the case 1° difluoroamination, HF elimination to the nitrile **9** would certainly prevail and “plain-old” styrene, **10**, would result. So, cumene appears to react as in Scheme 4 and a 3rd mechanistic end-route has been observed for our 3rd substrate class.

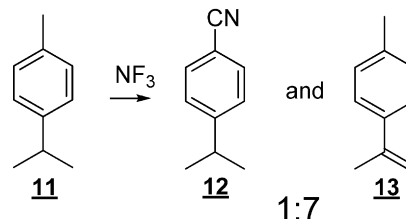
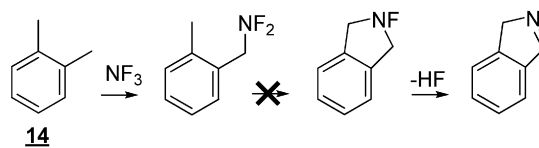
2.4. Reaction of NF_3 with *cymene*: selectivity for 3° versus 1°

p-Cymene, **11**, is an aromatic molecule with a 1° substituent at one end and a 3° substituent at the other end. The structure of *p*-cymene offers the opportunity to perform a competitive selectivity test of the NF_3 reaction on a single molecule. Reacting *p*-cymene under NF_3 -lean conditions afforded nitrile **12** and the α -methyl styrene **13** (as dimer) in a 1:7 mole ratio (Scheme 6). This is a high selectivity akin to that observed for Cl radical at 100°C [14].

2.5. Other bifunctional substrates

We investigated the reactions of *ortho*-xylene, **14**, with NF_3 to determine whether the rate of HF elimination from an intermediate difluoroaminobenzyl would be slow enough to allow for a second, intramolecular, fluoroamination to occur as in Scheme 7.

In practice, *o*-toluonitrile and phthalonitrile (3:1) were the only products isolated, indicative of mono- and disubstitution, respectively. None of the isoindole that would result from intramolecular substitution was observed.

Scheme 6. Selectivity of NF_3 reaction.

Scheme 7. Unobserved intramolecular fluoroamination.

As a cross-check, *p*-xylene was subjected to the same NF_3 reaction conditions. In this case monosubstitution was less prevalent to disubstitution (2:3). In addition, some alkyl-alkyl radical coupling product was observed (*o*-xylyl-xylene).

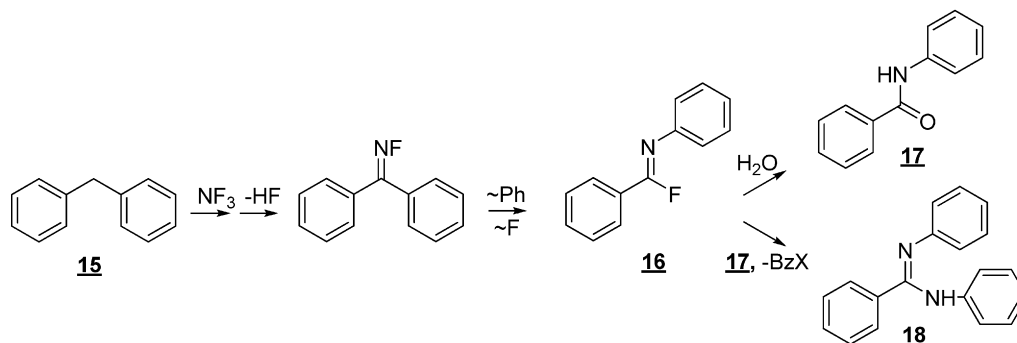















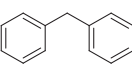
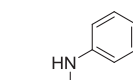
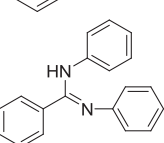
Scheme 8. Reaction of NF_3 with diphenylmethane.

Table 1
Products and yield of NF₃ reactions.

Substrate	Product(s)	Yield (%)
		46
		56
		59
	 	66
	 	39
	 	63
	 	53

2.6. Diphenylmethane

Diphenylmethane, **15**, reacted with NF₃ to produce two products. The major product was benzanilide, **17**, isolated in 45% yield, as the 4:3 co-precipitate with diphenylmethane. Again, this product is the result of difluoroamine formation, HF elimination and Beckmann Rearrangement, but without fragmentation (Scheme 8). This is the first example in which a hydrolysis product has been isolated in appreciable amounts. The second product was N¹,N²-diphenylbenzimidine, **18**, isolated in 7.5% yield and identified by X-ray crystallography [13]. Condensation of benzanilide, **17**, with iminium fluoride, **16**, followed by loss of the benzoyl group is the likely source of this material. We isolated small amounts of benzoyl fluoride, anhydride and benzoic acid which support this route.

3. Conclusion

At 400 °C, NF₃ reacts with benzylic substrates to generate intermediate N,N-difluorobenzylamines. These unstable amines decompose by differing mechanisms based on their order of substitution. Primary difluoroamines decompose by exuding HF to generate nitriles (i.e. toluene, xylenes). Secondary difluoroamines decompose by rearranging and eliminating R-F (i.e. ethylbenzene, diphenylmethane), and tertiary difluoroamines decompose by the apparent elimination of HNF₂ (i.e. cumene, cymene). See Table 1.

It was the goal of this project to find a means by which waste NF₃ could be utilized in a manner in which valuable products might be generated. The expectation was to make fluorobenzylic compounds such as benzotrifluoride. In reality, we have discovered that the product profile is composed of nitriles, amides, and α-methylstyrene dimers, depending on substrate. Nitriles and amides have utility as synthetic building blocks and, surprisingly, the α-methylstyrene dimers are valued components of dielectric fluids. The results of this study are encouraging.

4. Experimental

4.1. General

Cumene, cymene, diphenylmethane, ethylbenzene and xylenes were purchased from Aldrich. Toluene was Sunnyside distilled from CaH₂. Nitrogen trifluoride was supplied by Fluoromar, LLC.

Reactions were performed in a single 1" (2.5 cm) diameter tubular reactor, 24" (61 cm) long, with two electrically heated temperature zones of equal length. An internal thermocouple array monitored the reactor temperature at five equally spaced points. The reactor was fed via a vaporizer/preheater of similar configuration in 1" (1.25 cm) diameter. The reactor was charged with CrF₃-on-carbon pellets that had been previously used to exhaustion in chlorofluorination reactions. This "spent" CrF₃-on-carbon was chosen for the reactor bed as it was expected to be resistant to degradation by NF₃ and devoid of any oxidizing power (a control experiment on toluene, absent NF₃, yielded unchanged toluene with no oxidation or disproportionation observed). The reactor bed was pre-heated to 385 °C under a flow of 50 ml/min N₂. This N₂ flow was maintained throughout the experiments as a precaution against pooling of reagents within the preheating system in the event of flow stoppages. A backpressure of 1 atm was maintained. The vaporizer/preheater temperature was controlled to maintain a vapor temperature 10 °C above the boiling point of the organic feedstock. The feedstock (i.e. toluene), NF₃ and N₂ were all fed together to the vaporizer/preheater and through the reactor. An exotherm was always observed and the NF₃ feed was controlled so as to keep the temperature of all internal thermocouples under 425 °C. Typically NF₃ feeds did not exceed 50 mole%. Generally there would be one or two thermocouples indicating the exotherm and hence the location of the reaction. Product was collected through a cold water condenser, washed with water to remove HF, neutralized with saturated NaHCO₃ and dried over Na₂SO₄. Unreacted starting material and product fractions were separated by fractional distillation and sometimes silica gel column chromatography.

Products were identified by ¹H and ¹³C and ¹⁹F NMR performed on a Bruker DPX-250. MS was performed on an Agilent 6210 Time-of-Flight spectrometer.

4.2. Cautionary notes

Nitrogen trifluoride is toxic by inhalation and should only be used in a well ventilated environment. In addition, trace by-products may be toxic and concentrated during distillation.

NF₃ is an oxidant and care must be taken to ensure operations outside the explosivity limits of the NF₃/hydrocarbon mixture. It is advisable that all metal surfaces be fluoride passivated. In instances where the NF₃ ratio exceeded 50 mole% and/or reactor inlet temperatures raised much beyond the boiling point of the substrate *detonations were observed* in the preheater system. In an instance where the NF₃ ratio was 100 mole%, an apparent NF₃ flame initiated at the NF₃/toluene mixing point (stainless steel tee) as evidenced by the tee becoming literally red-hot (700 °C) [15].

Anhydrous HF is a by-product of these reactions. Anhydrous HF causes *instantaneous* severe burns to the skin and mucous membranes. HF should be handled with full PPE protection. An ample supply of HF antidote gel should be kept on hand before handling HF. See reference for burn treatment procedures [16].

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